

ABSTRACT OF THE DISCLOSURE

A method for manufacturing a minute structure comprises a step of forming an ionizing radiation decomposing type positive type resist layer including a methyl isopropenyl ketone as a first positive type photosensitive material layer to be sensitized by an ionizing radiation of a first wavelength range, a step of forming an ionizing radiation decomposing type positive type resist layer including a photosensitive material of a copolymer obtained by the copolymerization of an ester methacrylate and a methacrylic acid, with the weight average molecular weight of the copolymer of 50,000 to 300,000 and the ratio of the methacrylic acid included in the copolymer of 5 to 30% by weight as a second positive type photosensitive material layer to be sensitized by an ionizing radiation of a second wavelength range on the first positive type photosensitive material layer, a step of forming a desired pattern in the above-mentioned second positive type photosensitive material layer as the upper layer by decomposing reaction only in the desired area of the above-mentioned second positive type photosensitive material layer without decomposing reaction of the above-mentioned first positive type photosensitive material layer by directing an ionizing radiation of the above-mentioned second wavelength range via a

mask to the substrate surface with the first and second positive type photosensitive material layers formed, and development using a developing solution, and then, a step of forming a desired pattern in the

5 above-mentioned first positive type photosensitive material layer as the lower layer by decomposing reaction of a predetermined area of at least the above-mentioned first positive type photosensitive material layer by direction an ionizing radiation of

10 the above-mentioned first wavelength range via a mask to the substrate surface with the first and second positive type photosensitive material layers formed, and development, successively, characterized in that a pattern of a convex shape is manufactured in the

15 substrate by executing the above-mentioned steps.